

B. Amendment to the Claims

Please amend claim 8 and add new claims 13-16 as follows.

1. (Original) A method of manufacturing a structure with pores, comprising the steps of:
  - (A) disposing a lamination film on a substrate, the lamination film comprising insulating layers and a layer to be anodically oxidized and containing aluminum as a main composition; and
  - (B) performing anodic oxidation starting from an end surface of the lamination film to form a plurality of pores having an axis substantially parallel to a surface of the substrate,

wherein the layer to be anodically oxidized is sandwiched between the insulating layers, and a projected pattern substantially parallel to the axis of the pores is formed on at least one of the insulating layers at positions between the pores.
2. (Original) A method according to claim 1, wherein the layer to be anodically oxidized is made of aluminum.
3. (Original) A method according to claim 1, wherein at least one of the insulating layers is formed by anodic oxidation.
4. (Original) A method according to any one of claims 1 to 3, wherein a height of the projected pattern of the insulating layer is 1/10 or more of a thickness of the layer to be anodically oxidized.

5. (Original) A method according to any one of claims 1 to 3, further comprising a step of filling a filler in each of the pores after said step of performing anodic oxidation.

6. (Original) A method according to claim 5, wherein said step of filling a filler is performed by plating.

7. (Original) A method according to any one of claims 1 to 3, further comprising a step of forming an electrode layer connected to a bottom of each of the pores.

8. (Currently Amended) A structure with pores formed by the method comprising the steps of:

disposing a lamination film on a substrate, the lamination film comprising insulating layers and a layer to be anodically oxidized and containing aluminum as a main composition; and

performing anodic oxidation starting from an end surface of the lamination film to form a plurality of pores having an axis substantially parallel to a surface of the substrate,

wherein the layer to be anodically oxidized is sandwiched between the insulating layers, and a projected pattern substantially parallel to the axis of the pores is formed on at least one of the insulating layers at positions between the pores according to any one of claims 1 to 3.

9. (Original) A structure according to claim 8, further comprising an electrode layer connected to a bottom of each of the pores.

10. (Original) A method of manufacturing a structure with pores comprising the steps of:
- (A) sandwiching a film containing aluminum as a main composition between first and second insulating films; and
- (B) anodically oxidizing the film having aluminum as the main composition along a direction substantially perpendicular to a direction of making the first and second insulating films face each other,
- wherein projections are formed on a surface of at least one of the first and second insulating films in contact with the film containing aluminum as the main composition, the projections controlling a pitch between the pores to be formed by anodic oxidation.

11. (Original) A structure with pores comprising:
- (A) a film sandwiched between first and second insulating films, said film containing aluminum oxide as a main composition;
- (B) a plurality of pores disposed in said film containing aluminum as the main composition, a longitudinal direction of each of said pores being a direction substantially perpendicular to a direction of making said first and second insulating films face each other, and each of said pores being disposed substantially parallel; and
- (C) a projected pattern disposed among said pores,
- wherein said projected pattern is made of an insulating member in contact with said first or second insulating film and has a line shape substantially parallel to a longitudinal direction of each of said pores.

12. (Original) A structure according to claim 11, wherein said projected pattern is made of a partial region of said first or second insulating film.

13. (New) A structure according to claim 8, wherein the layer to be anodically oxidized is made of aluminum.

14. (New) A structure according to claim 8, wherein at least one of the insulating layers is formed by anodic oxidation.

15. (New) A structure according to claim 13, further comprising an electrode layer connected to a bottom of each of the pores.

16. (New) A structure according to claim 14, further comprising an electrode layer connected to a bottom of each of the pores.